



Solid • Smart • Stable

COAT ■ DEVELOP ■ BAKE ■ WEE

A leading supplier of
photoresist process and
cleaning equipment

Smart tools that maximize performance and lower cost of ownership

S-Cubed provides higher reliability, more functionality and a smaller footprint - all at a lower cost. We do this by eliminating “non value added” hardware and by the use of advanced controls, software and robotics.

Applications

- Patterned Sapphire Substrates (PSS)
- BEOL
- MEMS
- LED/OLED
- III - V Telecom Materials
- PV Photo Voltaics
- Mask Cleaner



S-Cubed System Features

- Small footprint
- Color LCD touchscreen
- One or two spin modules
- Unlimited process storage capabilities
- Remote data collection and control
- Stacked thermal modules
- Multiple size substrates without change
- Servo motion control
- Process substrates up to 300 mm
- Proven modular design
- Ultra high reliability

For more information on all products including the new Flexi III™ system, the TruClean™ double sided scrubbing systems, and Cyclone™ spin processors, please visit our website: www.s-cubed.com.



FLEXI™

Photoresist Processing Systems

Capable of processes including: Prime, Chill, Coat, Bake, PEB, WEE, Develop - with up to 50 wafers on the tool this work horse can do it all.



FLEXI BASIC™

Photoresist Processing Systems

Built on the Flexi III chassis this tool minimizes cost by substituting pneumatic process actuation for servo process actuation, while offering adjustable rather than fully programmable functionality.



FORCE 300™

Utilizing a double end effector high speed robot the Force 300 offers the highest productivity for 300mm wafer processing. The tool is capable of system expansion with multiple robots and modules.



CYCLONE™

Ideal for cleaning after dicing operations or for mask cleaning.



WEE™

Double Sided Scrub System

PVA and/or nylon brushes for double and single sided wafer or substrate scrubbing. Manual or fully automated cassette to cassette.



PRC 6625™

Back Side Reticle Cleaner

The PRC 6625 (patent pending) provides a means of cleaning the back side of a Pelliculized Reticle without affecting nor even touching the Pelliculized side of the reticle.